

The IQubits project for quantum computing in Si and SiGe MOSFETs

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https://www.iqubits.eu

A NEW ROUTE FOR THE SPIN QUBIT







A NEW ROUTE FOR THE SPIN QUBIT

OLD PARADIGM

- QD in III-V semiconductor heterostructures
- Device implementations developed within academic-scale laboratories
- Magnetically controlled spin manipulation

NEW PARADIGM

- ≫ Silicon
- > Commercial devices with industrial fabrication as starting point
- ➢ Fully-electrical control of the spin qubit





S. Bonen et al., IEEE Electron Device Lett., 40, 127-130 (2019)

SILICON AS HOST MATERIAL



ELECTRON SPIN QUBITS



- vertical confinement + valley splitting due to sharp interfaces or dopants
- \gg weak SO coupling in CB
- \rightarrow spin qubit
- $\rightarrow\,$ not sensitive to charge noise



 \rightarrow magnetically-driven spin manipulation



J Yoneda, Nat. Comm. 12 4114 (2021)

HOLE SPIN QUBITS





- \gg HH, LH states degenerate at **k**=0
- Splitting of J=3/2 bands due to size quantization
- ≫ static B to lift Kramers degeneracy
- ≫ large SO coupling
- \rightarrow pseudo-spin qubit
- \rightarrow sensitive to charge noise
- $\rightarrow\,$ all-electrical spin manipulation



SILICON AS HOST MATERIAL



ideal for large arrays of QDs \rightarrow error correction codes

IQUBITS PROJECT collaborative R.I.A. funded by Horizon 2020 [FET-Open programme]

OBJECTIVES: integration + scaling

- >> proposes *commercial* devices for spin qubit
- >> qubit *co-integrated* with control electronics (spin manipulation, readout...)

Fully-Depleted- Silicon-On Insulator (FDSOI) MOSFETs Si and SiGe UNDOPED channel



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Ultra-scaled devices 10 nm channel length (increase ΔE)



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Fully-Depleted- Silicon-On Insulator (FDSOI) MOSFETs Si and SiGe UNDOPED channel

Ultra-scaled devices 10 nm channel length (increase ΔE)

Multi-scale simulation From device electrostatic up to qubit operations



DOWNSCALED Si FDSOI pMOSFETs

Ginestra (MDLab)



Bellentani et al. , arXiv:2106.04940 (2021)

NUMERICAL APPROACH FOR HOLE SPIN QUBIT



Towards hole-spin qubits in Si pMOSFETs within a planar CMOS foundry technology

L. Bellentani¹, M. Bina², S. Bonen³, A. Secchi¹, A. Bertoni¹,

S. Voinigescu³, A. Padovani², L. Larcher², and F. Troiani¹ ¹S3, Istituto Nanoscienze-CNR, Modena, Italy

²Applied Materials - MDLx Italy R&D, Reggio Emilia, Italy and

³Edward S. Rogers Snr. Department of Electrical and Computer Engineering, University of Toronto, Toronto, Canada

- \gg **QD formation** in the Si channel of downscaled pMOSFETs
- \gg **Initialization** of the qubit in the ground state
- \gg **Fully-electrical spin manipulation**



6X6 k.p MODELING IN THE EFA SCHEME

Second-order perturbation of k.p Hamiltonian at k=0 + Hso for diamond lattice

Basis set @
$$\Gamma$$
→ p-like orbitals (l=1) + spin (s=1/2) → J=3/2, J=1/2

$$\{|b\rangle\} = \{\underbrace{|\frac{3}{2}, +\frac{3}{2}}_{hh+}, \underbrace{|\frac{3}{2}, +\frac{1}{2}\rangle, |\frac{3}{2}, -\frac{1}{2}\rangle}_{hh+}, \underbrace{|\frac{3}{2}, -\frac{3}{2}\rangle}_{hh-}, \underbrace{|\frac{1}{2}, +\frac{1}{2}\rangle, |\frac{1}{2}, -\frac{1}{2}\rangle}_{hh-}\} \qquad \Delta = 44 \text{ meV}$$





.

6X6 k.p MODELING IN THE EFA SCHEME

> Envelope Function Approximation for nano-confining potential U(r)

$$\mathcal{H}(oldsymbol{r},oldsymbol{k}) = \mathcal{H}_{oldsymbol{k}} + U(oldsymbol{r}) \stackrel{\mathsf{LAPACK}}{\longrightarrow} \Psi_m(oldsymbol{r}) = \sum_b \psi_{m,b}(oldsymbol{r}) \langle oldsymbol{r}|b
angle$$

> Full-treatment of the magnetic contribution (Zeeman + vector potential)



$$U(\mathbf{r}) [TCAD]$$

$$\mathcal{H}_{m{k}}
ightarrow \mathcal{H}_{m{k}-rac{e}{h}m{r} imesm{B}/2} + \mathcal{Z} = \mathcal{H}_{m{k}} + \mathcal{Z} + \mathcal{H}_p + \mathcal{H}_d \ \propto B \propto B^2$$
 H_B

CHARACTERISTIC FREQUENCIES OF SPIN QUBIT



ALL ELECTRICAL X,Y AND Z ROTATIONS

Electric-Dipole-induced Spin Resonance (X, Y)

$$egin{aligned} \delta VG(t) &= V_{ac}\cos(2\pi f_L\,t+\phi) \ \delta U(m{r}) &= U_{VG+\delta VG(t)}(m{r}) - U_{VG}(m{r}) \ f^X_R &= rac{1}{h} |\langle 1 \Uparrow | \delta U(m{r}) | 1 \Downarrow
angle | \ \phi &= 0 o X \ \phi &= rac{\pi}{2} o Y \end{aligned}$$

≫ DC pulse (Z)

 $\delta VG(t) = V_{DC}$

$$f_R^Z = rac{1}{2h} |\langle 1 \Uparrow | \delta U(m{r}) | 1 \Uparrow
angle - \langle 1 \Downarrow | \delta U(m{r}) | 1 \Downarrow
angle |$$



$$|\Psi(0)
angle=\cosrac{ heta}{2}|0
angle+e^{iarphi}\sinrac{ heta}{2}|1
angle$$

 $|\Psi(t)
angle=e^{-i\omega_R\sigma_Z t}|\Psi(0)
angle \ \ |\Psi(t)
angle=e^{-i\omega_R\sigma_X t}|\Psi(0)
angle$





QD FORMATION: SINGLE HOLE SPECTRUM



INITIALIZATION: LARMOR FREQUENCY

$$f_L(B, heta,\phi)=(E_{1\Uparrow}-E_{1\Downarrow})/h$$



60-20 GHz at B=1T \rightarrow OK FOR EDSR





SPIN MANIPULATION: RABI FREQUENCIES



B=1 T

- » ≈ 100 MHz @ B=1 T
- \gg SO non negligible
- ≫ Strongly anisotropic Rabi frequency
- ≫ almost anti-correlated fRX and fRZ

$$f_R^{XZ} = \left(rac{1}{f_R^X} + rac{1}{f_R^Z}
ight)^{-1}$$

- ≫ fRZ=0 sweet spot against electrical noise
- ➢ Alternative Pauli Z-gate

$$Z(\phi)=Y(\pi/2)X(\phi)Y(-\pi/2)$$

INSIGHTS FROM THE G-MATRIX

- \gg Linearity in B \rightarrow Effective two-level description H_{I}
- \gg Linearity in VG ightarrow g-matrix linearly perturbed $\hat{g}(V)$

 $egin{aligned} H_B &= rac{1}{2} \mu_B{}^t oldsymbol{\sigma} \cdot \hat{g} oldsymbol{B} & \{ |1 \Downarrow
angle, |1 \Uparrow
angle \} \ \hat{g}(VG) &= \hat{g}(VG_0) + \hat{g}'(VG_0) \delta VG \end{aligned}$

$$egin{aligned} H(V_G,B;t) &= oldsymbol{\sigma} \cdot \left[rac{1}{2} \mu_B \hat{g}(VG_0) \cdot oldsymbol{B}
ight] + oldsymbol{\sigma} \cdot \left[rac{1}{2} \mu_B \hat{g}'(VG_0) \cdot oldsymbol{B}
ight] \delta VG(t) \ & ext{Larmor vector } oldsymbol{h} \Omega & ext{ gate-voltage derivative } oldsymbol{h} \Omega' \ & \Omega' &= \Omega'_\perp + \Omega'_\parallel \end{aligned}$$

$$egin{aligned} \Omega'_{\parallel} &
ightarrow f^Z_R(B, heta,\phi) = rac{\mu_B B V_{ac}}{2hg^*} |(\hat{g}'m{b})\cdot(\hat{g}m{b})| \ \Omega'_{\perp} &
ightarrow f^X_R(B, heta,\phi) = rac{\mu_B B V_{ac}}{2hg^*} |(\hat{g}'m{b}) imes(\hat{g}m{b})| \end{aligned}$$

INSIGHTS FROM THE G-MATRIX

APPROX: Diagonal g-matrix and g'-matrix (symmetries preserved)

 $\rightarrow \delta VG$ modulates Zeeman split only (g-TMR)

INSIGHTS FROM THE G-MATRIX

$$egin{aligned} heta_{R,max}^X &= rctanigg(\sqrt{|g_{ot}/g_{\|}|}igg) \ f_R^{X,max} &= rac{\mu_B B V_{ac}}{2h} rac{|g_{\|}'g_{ot}-g_{ot}'g_{\|}|}{|g_{\|}|+|g_{ot}|} \end{aligned}$$

$$egin{aligned} heta^Z_{R,zero} &= rctanigg(\sqrt{|g_ot g_ot g_ot g_ot g_ot g_ot g_out g_out g_out |}|igg) \ f^{Z,max}_R &= rac{\mu_B B V_{ac}}{2h} \max_{lpha \in x,y,z} |g'_lpha| \end{aligned}$$

- ➢ Rabi frequencies are dominated by g-TMR
- >> Optimal orientation for fast electrical control
- \gg Anticorrelation between fRX and fRZ

$$g'_{\perp}pprox g'_{\parallel}
ightarrow heta^X_{R,max}pprox heta^Z_{R,zero}$$



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- **QD formation** in the Si channel of downscaled pMOSFETs
- **Initialization** of the qubit in the ground state
- **Fully-electrical spin manipulation**

+ SO is relevant

+ beyond Zeeman contribution are relevant

+ g-TMR dominates

+ sweet spots against electrical noise

TOWARDS SiGe DEVICES and DQDs

- \gg Compatible with Si fabrication technique
- \gg Higher carrier mobility
 - \rightarrow increase energy mode splitting
 - \rightarrow Relax lithographic requirements
- > Compressive strain due to Ge concentration (Bir-Pikus Hamiltonian)
- ➢ No Ge nanoclustering in Si matrix

"High-throughput investigation of the electron transport properties in Si1-xGex alloys" BAMIDELE I. ADETUNJI, ANDREW SUPKA, MARCO FORNARI, AND ARRIGO CALZOLARI

- \gg Downscaled double QD SiGe devices
 - $\rightarrow\,$ horizontally vs vertically coupled QDs
 - \rightarrow READOUT with gate reflectometry







RELATED WORK ON TWO-HOLE QUBITS

> Numerical and analytical investigation of interacting holes in Si/Ge DQDs

"Interacting holes in Si and Ge double quantum dots: From a multiband approach to an effective-spin picture", A. Secchi, L. Bellentani, A. Bertoni, and F. Troiani Phys. Rev. B **104**, 035302 (2021)

> Numerical approach for Coulomb integrals with **interband scattering processes**

"Inter- and intra-band Coulomb interactions between holes in Silicon nanostructures", A. Secchi, L. Bellentani, A. Bertoni, and F. Troiani arXiv:2010.01332 (2020)

$$V_{\set{
u}} = \sum_{\{b\}} \int dm{r} \int dm{r}' \psi^*_{
u_1,b_1}(m{r}) \psi^*_{
u_2,b_2}(m{r}') W_{\{b\}}(m{r}-m{r}') \psi_{
u_3,b_3}(m{r}') \psi_{
u_4,b_4}(m{r})$$

numerically demanding \rightarrow Fourier transform method

THE CONSORTIUM

University of Toronto Aarhus University INDUSTRIAL MANIFACTURING AND IC DESIGN access to Globalfoundry

CNR-Nano (S3, Modena)

DEVICE PHYSICS AND MODELLING

atomistic modeling of nanostructures and electric properties simulation of quantum gates and readout/manipulation

IMT Bucarest NANOFABRICATION ultra-scaleld devices

FORTH Crete

MATERIALS ENGINEERING AND GROWTH

III-N growth and device development

MDLab

TCAD SIMULATION

device modelling and simulation of QD electrostatic















THANK YOU FOR YOUR ATTENTION

Related publications

- L. Bellentani, A. Secchi, A. Bertoni and F. Troiani, Towards hole-spin qubits in Si pMOSFETs within a planar CMOS foundry technology, arXiv:2106.04940 (2021)
- A. Secchi, L. Bellentani, A. Bertoni, and F. Troiani, Interacting holes in Si and Ge double quantum dots: From a multiband approach to an effective-spin picture, Phys. Rev. B 104, 035302 (2021)
- A. Secchi, L. Bellentani, A. Bertoni, and F. Troiani, Inter- and intra-band Coulomb interactions between holes in Silicon nanostructures, arXiv:2010.01332 (2020)

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